

Notice of References Cited	Application/Control No. 08/960,431	Applicant(s)/Patent Under Reexamination SUGIYAMA ET AL.
	Examiner Jacob K. Ackun Jr.	Art Unit 3723

U.S. PATENT DOCUMENTS

*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A US-3,568,377	03-1971	Blohm et al.	451/444
*	B US-3,594,963	07-1971	Beasley, George A.	51/293
*	C US-3,710,517	01-1973	Valerio et al.	451/42
*	D US-3,785,094	01-1974	Holzhauer, Rudolf	451/532
*	E US-5,154,021	10-1992	Bombardier et al.	451/444
*	F US-5,172,681	12-1992	Ruark et al.	125/38
*	G US-5,235,959	08-1993	Frank et al.	125/11.01
H	US-			
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FOREIGN PATENT DOCUMENTS

*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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NON-PATENT DOCUMENTS

*	Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)	
*	U	Semiconductor International, Mar. 1992, pp.44-48, Peter H. singer, Senior Editor.
*	V	Spin-On Glass for Dielectric Planarization by Satish K. Gupta, distributed through the courtesy of Allied-signal Inc., Milpitas, CA.
*	W	Solid State Technology May 1992, Sematech Inc., Austin, Texas. Planarizing Interlevel Dielectrics by Chemical-Mechanical Polishing.
*	X	Electronics Materials, Mar. 1994, pp91-96.

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Speedfam CMP-V Planarization System, The Competitive Edge. 0.35, Micron Line Width Design Rule.
	V	
	W	
	X	

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